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SiO_2薄膜的液相沉积及特性

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摘　要:将基片浸入到低温SiO_2过饱和的六氟硅酸(H_2SiF_6)溶液中,在其表面上沉积SiO_2薄膜。这种新的生长工艺称之为液相沉积(LPD)。本文着重介绍LPD工艺及LPD SiO_2薄膜的特性。

关键词:液相沉积;SiO_2;薄膜

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IPD OF SiO_2 FILM AND ITS PROPERTIES

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Abstract:A silica(SiO_2) film was deposited on the surface of a sub-6 strate by immersing it into hydro-fluosilisic acid(H_2SiF_6) solution supersaturated with silicagel at low temperature.This process is called liquid phase deposition(LPD).This new LPD process and some properties of the LPD SiO_2 film are presented in this paper.

Keywors:liquid phase deposition;SiO_2;film

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